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Optical Micro- and Nanometrology in Microsystems Technology II

**Christophe Gorecki
Anand K. Asundi
Wolfgang Osten**
Editors

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Contents

ix Conference Committee

SESSION 1 DIGITAL HOLOGRAPHY

- 6995 02 **Sensitivity increase in digital holographic interferometry (Invited Paper)** [6995-01]
N. Demoli, K. Šariri, Institute of Physics (Croatia); I. Sović, Univ. of Zagreb (Croatia);
M. Torzynski, H. Halaq, D. Vukičević, Univ. Louis Pasteur (France)
- 6995 03 **Dual-wavelength digital holographic microscopy with sub-nanometer axial accuracy**
[6995-02]
J. Kühn, F. Charrière, Ecole Polytechnique Fédérale de Lausanne (Switzerland); T. Colomb,
DP-CHUV (Switzerland); F. Montfort, E. Cuhe, Y. Emery, Lyncée Tec SA (Switzerland);
P. Marquet, DP-CHUV (Switzerland); C. Depeursinge, Ecole Polytechnique Fédérale de
Lausanne (Switzerland)
- 6995 04 **Undersampled digital holographic interferometry** [6995-03]
H. Halaq, Univ. Louis-Pasteur (France); N. Demoli, I. Sović, K. Šariri, Institute of Physics
(Croatia); M. Torzynski, D. Vukičević, Univ. Louis-Pasteur (France)
- 6995 05 **Digital holography in combination with diffraction grating to get super-resolution** [6995-04]
M. Paturzo, F. Merola, S. Grilli, Istituto Nazionale di Ottica Applicata (Italy); S. De Nicola,
Istituto di Cibernetica Eduardo Caianiello (Italy); P. Ferraro, Istituto Nazionale di Ottica
Applicata (Italy)
- 6995 06 **Phase map retrieval in digital holography: avoiding the under-sampling effect by a lateral
shear approach** [6995-05]
P. Ferraro, C. Del Core, L. Miccio, S. Grilli, S. De Nicola, A. Finizio, Istituto Nazionale di Ottica
Applicata and Istituto di Cibernetica Eduardo Caianiello (Italy) and LENS European Lab.
for Non Linear Spectroscopy (Italy); G. Coppola, Istituto Microelettronica
e Microsistemi (Italy)
- 6995 07 **Application of light emitting diodes in digital holographic microscopy** [6995-06]
S. Stürwald, B. Kemper, C. Remmersmann, P. Langehanenberg, G. von Bally, Univ.
of Münster (Germany)
- 6995 08 **Adaptive measurement of deformation and shape by compensation using TV holography
and digital holography** [6995-08]
J. Kornis, B. Béki, R. Séfel, Budapest Univ. of Technology and Economics (Hungary)

SESSION 2 NANOSCALE METROLOGY AND SENSORS FOR NEAR-FIELD MICROSCOPY

- 6995 09 **Sensitivity enhancement of integrated optical near field sensors** [6995-09]
J. Hahn, F. Fecher, J. Petter, T. Tschudi, Darmstadt Univ. of Technology (Germany)

- 6995 0A **Integrated optic Michelson interferometer for sensors application** [6995-10]
P. Marć, Military Univ. of Technology (Poland) and Institut FEMTO-ST (France); C. Gorecki, Ł. Nieradko, Institut FEMTO-ST (France)
- 6995 0B **Development features in large-range nanoscale coordinate metrology** [6995-11]
M. Gruhlke, C. Recknagel, H. Rothe, Helmut-Schmidt Univ. (Germany)
- 6995 0D **Electron beam nanolithography and testing: ways of increasing the resolution and the throughput** [6995-13]
V. A. Zlobin, All-Russian Electrotechnical Institute (Russia)

SESSION3 INSPECTION OF MEMS

- 6995 0E **AIN driven microcantilever actuators: modeling, fabrication, characterization** [6995-14]
K. Krupa, Warsaw Univ. of Technology (Poland) and Univ. de Franche-Comté (France); M. Jóźwik, Warsaw Univ. of Technology (Poland); A. Andrei, Ł. Nieradko, C. Gorecki, P. Delobelle, L. Hirsinger, Univ. de Franche-Comté (France)
- 6995 0F **Characterization of MEMS cantilevers using lensless digital holographic microscope** [6995-15]
V. R. Singh, Nanyang Technological Univ. (Singapore); A. Andrei, C. Gorecki, L. Nieradko, FEMTO-ST (France); A. Asundi, Nanyang Technological Univ. (Singapore)
- 6995 0G **Nondestructive determination of drying deformations in cement paste by means of ESEM and digital image analysis** [6995-16]
D. Jankovic, Delft Univ. of Technology (Netherlands)
- 6995 0H **Numerical simulations of interferometrical deformation measurements in multi-layered objects** [6995-17]
K. Gastinger, SINTEF ICT (Norway); P. Løvhaugen, Univ. of Tromsø (Norway); O. Hunderi, Norwegian Univ. of Science and Technology (Norway)
- 6995 0I **Fusion of micro-metrology techniques for the flexible inspection of MEMS/MOEMS assembly** [6995-18]
R. Schmitt, A. Pavim, RWTH Aachen Univ. (Germany)

SESSION 4 HIGH RESOLUTION METROLOGY AND SPECIALISED TECHNIQUES

- 6995 0J **Benchmarking instrumentation tools for the characterization of microlenses within the EC Network of Excellence on Micro-Optics (NEMO) (Invited Paper)** [6995-19]
H. Ottevaere, Vrije Univ. Brussel (Belgium); J. Schwider, Friedrich-Alexander-Univ. Erlangen-Nürnberg (Germany); J. Kacperski, Warsaw Univ. of Technology (Poland); L. Steinbock, Forschungszentrum Karlsruhe (Germany); K. Weible, SUSS MicroOptics SA (Switzerland); M. Kujawska, Warsaw Univ. of Technology (Poland); H. Thienpont, Vrije Univ. Brussel (Belgium)

- 6995 OK **Interest of second harmonic generation imaging to study collagenous matrix modification in osteoarthritis disease** [6995-20]
E. Werkmeister, N. de Isla, L. Marchal, Nancy Univ. (France) and Faculté de Médecine (France); D. Mainard, CHU Nancy (France); J.-F. Stoltz, Nancy Univ. (France), Faculté de Médecine (France), and CHU Nancy (France); D. Dumas, Nancy Univ. (France) and Faculté de Médecine (France)
- 6995 OL **Real time and in situ monitoring of microlenses fabricated with deep proton writing** [6995-21]
V. Gomez, H. Ottevaere, H. Thienpont, Vrije Univ. Brussel (Belgium)
- 6995 OM **Precision metrology length standard based on femtosecond stabilized laser** [6995-22]
R. Šmíd, O. Číp, J. Lazar, Institute of Scientific Instruments (Czech Republic)
- 6995 ON **A multipoint diffraction strain sensor using a micro-lens array: from theory to application** [6995-23]
J. Wang, A. Asundi, Nanyang Technological Univ. (Singapore)
- 6995 OO **Comparison of $^{127}\text{I}_2$ -stabilized frequency-doubled Nd: YAG lasers and evaluation of frequency shifts caused by iodine cells** [6995-24]
J. Hrabina, P. Jedlička, O. Číp, J. Lazar, Institute of Scientific Instruments (Czech Republic)

SESSION 5 TOPOGRAPHY AND SURFACE MEASUREMENTS

- 6995 OP **Characterization of materials and film stacks for accurate surface topography measurement using a white-light optical profiler (Invited Paper)** [6995-25]
X. Colonna de Lega, P. J. de Groot, Zygo Corp. (USA)
- 6995 OQ **Improved micro topography measurement by LCoS-based fringe projection and z-stitching** [6995-26]
X. Schwab, C. Kohler, K. Körner, Univ. Stuttgart (Germany); N. Eichhorn, GEFASOFT Automatisierung und Software GmbH (Germany); W. Osten, Univ. Stuttgart (Germany)
- 6995 OR **Photonic wires sidewall roughness measures using atomic force microscope capabilities** [6995-27]
R. Malureanu, L. H. Frandsen, Technical Univ. of Denmark (Denmark)

SESSION 6 SCATTEROMETRY AND DIFFUSION TECHNIQUES

- 6995 OT **Computational methods estimating uncertainties for profile reconstruction in scatterometry** [6995-29]
H. Gross, Physikalisch-Technische Bundesanstalt (Germany); A. Rathsfeld, Weierstrass Institute for Applied Analysis and Stochastics (Germany); F. Scholze, R. Model, M. Bär, Physikalisch-Technische Bundesanstalt (Germany)
- 6995 OU **On quasi-phase-conjugated arrays** [6995-30]
G. Kloos, Meilute (Germany)

- 6995 0V **Modeling reflection on coated steel surfaces** [6995-31]
V. Goossens, E. Stijns, N. Gotzen, Vrije Univ. Brussel (Belgium); S. Van Gils, ArcelorMittal R&D Industry Gent (Belgium); H. Terry, Vrije Univ. Brussel (Belgium)
- 6995 0X **Full-field analysis of a liquid crystal cell using a low birefringence polariscope** [6995-33]
W. Pin, A. Asundi, Nanyang Technological Univ. (Singapore)

SESSION 7 IMAGE RECONSTRUCTION AND SIGNAL PROCESSING

- 6995 0Y **Investigation of methods to set up the normal vector field for the differential method** [6995-34]
S. Rafler, P. Götz, M. Petschow, T. Schuster, K. Frenner, W. Osten, Univ. Stuttgart (Germany)
- 6995 0Z **Phase retrieval from the spectral interferograms by windowed Fourier transform** [6995-35]
P. Hlubina, J. Luňáček, D. Ciprian, R. Chlebus, M. Luňáčková, Technical Univ. Ostrava (Czech Republic)
- 6995 10 **Wrap-free phase retrieval using a series of intensity measurements produced by tuning the illumination wavelength** [6995-36]
P. Bao, F. Zhang, G. Pedrini, W. Osten, Univ. Stuttgart (Germany)
- 6995 11 **A Fourier-optics-based non-invasive and vibration-insensitive micron-size object analyzer for quality control assessment** [6995-37]
S. Sumriddetchkajorn, K. Chaitavon, National Electronics and Computer Technology Ctr. (Thailand)
- 6995 12 **Ultra-fast wavefront analyser for high volume production of camera modules lenses** [6995-46]
M. Cherrier, Trioptics France (France); I. Erichsen, A. Ruprecht, S. Krey, Trioptics GmbH (Germany)

POSTER SESSION

- 6995 13 **Pixel size determination of a monitor using moiré fringe** [6995-38]
M. Abolhassani, R. Daman, Univ. of Arak (Iran)
- 6995 14 **Accurate three-dimensional detection of micro-particles by means of digital holographic microscopy** [6995-40]
M. Antkowiak, N. Callens, C. Schockaert, C. Yourassowsky, F. Dubois, Univ. Libre de Bruxelles (Belgium)
- 6995 15 **Energy characteristics of excitons in InGaN/GaN heterostructures** [6995-42]
S. O. Usov, A. F. Tsatsul'nikov, W. V. Lundin, A. V. Sakharov, E. E. Zavarin, A.F. Ioffe Physico-Technical Institute (Russia); M. A. Sinitsyn, St. Petersburg Physico-Technical Ctr. (Russia); N. N. Ledentsov, A.F. Ioffe Physico-Technical Institute (Russia)
- 6995 16 **In-situ imaging of interlayer nanodeformation with improved differential confocal microscopy** [6995-43]
Z. Li, S. Gao, K. Herrmann, Physikalisch-Technische Bundesanstalt (Germany)

- 6995 17 **Investigation of high reflectivity optical phase-conjugation in BaTiO₃** [6995-45]
M. H. Majles Ara, Tarbiat Moallem Univ. (Iran); S. R. Hosseini, M. Abolhassani, Arak Univ.
(Iran)

Author Index

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Xiaoping Wu, University of Science and Technology of China (China)
Huimin Xie, Tsinghua University (China)

Session Chairs

- 1 Digital Holography
Wolfgang Osten, Universität Stuttgart (Germany)
- 2 Nanoscale Metrology and Sensors for Near-Field Microscopy
Anand K. Asundi, Nanyang Technological University (Singapore)
- 3 Inspection of MEMS
Christophe Gorecki, Université de Franche-Comté (France)
- 4 High Resolution Metrology and Specialised Techniques
Pietro Ferraro, Istituto Nazionale di Ottica Applicata (Italy)

- 5 Topography and Surface Measurements
Malgorzata Kujawska, Politechnika Warszawska (Poland)
- 6 Scatterometry and Diffusion Techniques
Nazif Demoli, University of Zagreb (Croatia)
- 7 Image Reconstruction and Signal Processing
Heidi Ottevaere, Vrije Universiteit Brussel (Belgium)